

DERWENT-ACC-NO: 2003-633521

DERWENT-WEEK: 200482

COPYRIGHT 2005 DERWENT INFORMATION LTD

TITLE: Semiconductor fabricating apparatus for supplying
process gas to inside of tube

INVENTOR: PARK, Y S

PATENT-ASSIGNEE: KOKUSAI ELECTRIC KOREA[KOKZ] , KOOK JE ELECTRIC CO
LTD [KOOKN]

PRIORITY-DATA: 2001KR-0070682 (November 14, 2001)

PATENT-FAMILY:

PUB-NO	PUB-DATE	LANGUAGE	PAGES
MAIN-IPC			
KR 444753 B	August 21, 2004	N/A	000
H01L 021/205			
KR 2003039670 A	May 22, 2003	N/A	001
H01L 021/205			

APPLICATION-DATA:

PUB-NO	APPL-DESCRIPTOR	APPL-NO	APPL-DATE
KR 444753B	N/A	2001KR-0070682	
November 14, 2001			
KR 444753B	Previous Publ.	KR2003039670	N/A
KR2003039670A	N/A	2001KR-0070682	
November 14, 2001			

INT-CL (IPC): H01L021/205

ABSTRACTED-PUB-NO: KR2003039670A

BASIC-ABSTRACT:

NOVELTY - A semiconductor fabricating apparatus for supplying process gas to the inside of a tube is provided to rapidly exhaust reaction gas and minimize generation of particles by making the flow path of the reaction gas short, and to improve uniformity by uniformly supplying the reaction gas regardless of the position in a process chamber.

DETAILED DESCRIPTION - A plurality of wafers are loaded into a boat (140).

A reaction furnace has a closed inner space into which the boat is loaded. A

shower head(120) uniformly sprays the reaction gas on the inner space of the reaction furnace, installed in the sidewall of the reaction furnace.

CHOSEN-DRAWING: Dwg.1/10

TITLE-TERMS: SEMICONDUCTOR FABRICATE APPARATUS SUPPLY PROCESS GAS TUBE

DERWENT-CLASS: U11

EPI-CODES: U11-C01B;

100

